

SCDA / PIAACMC status

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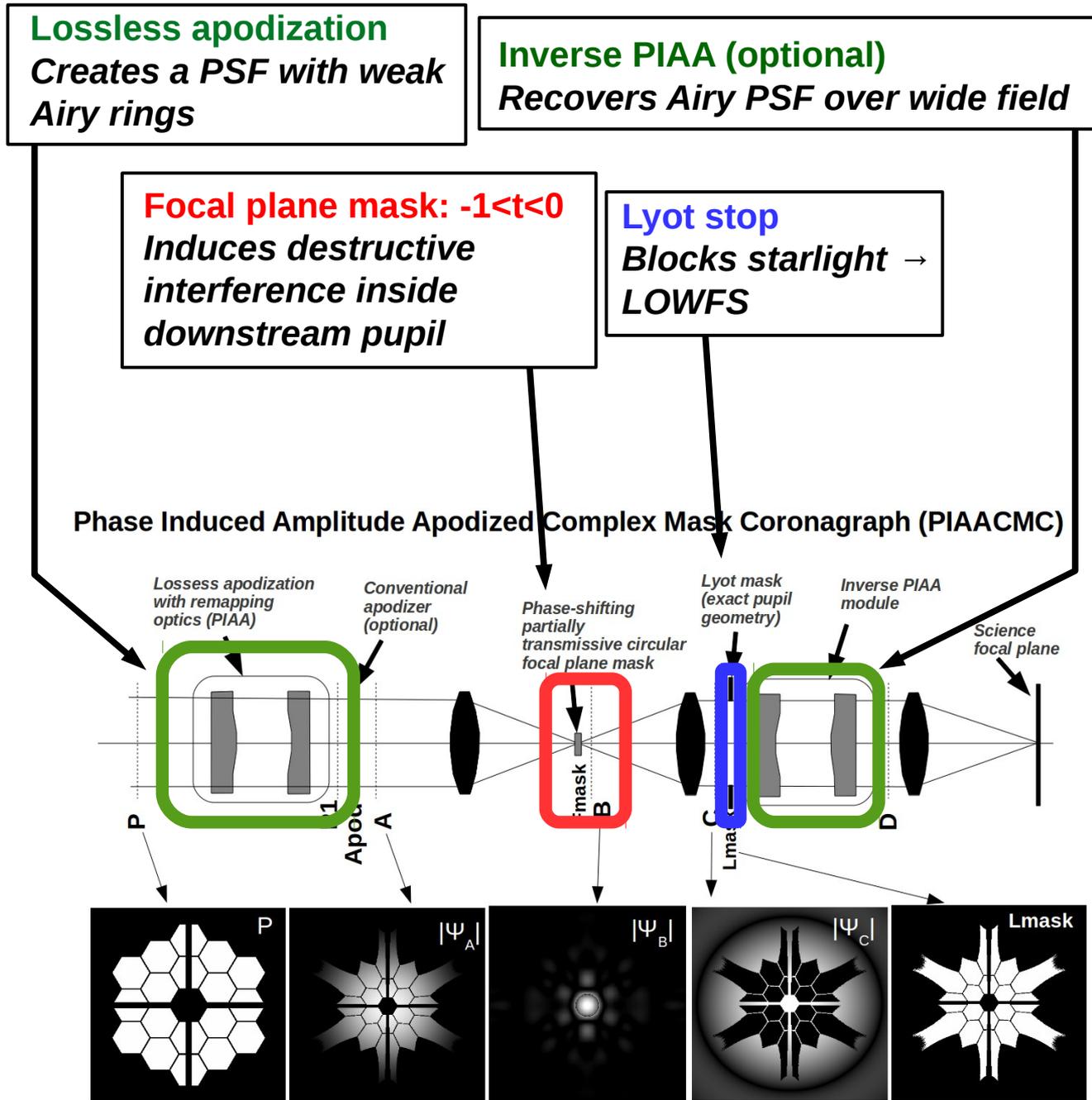
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Brian Kern

PIAACMC principle, theoretical performance

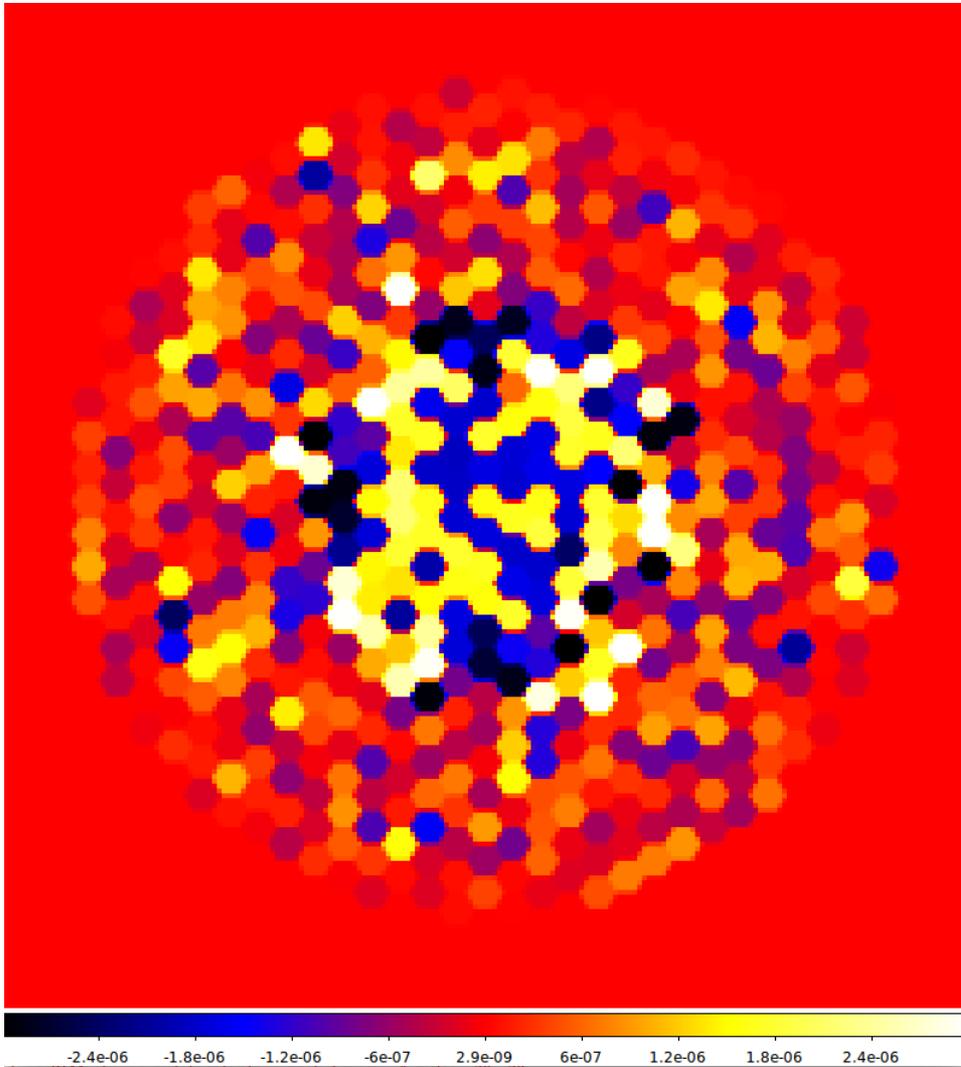
PIAACMC provides, for any aperture shape, full rejection (infinite contrast), 1.0 I/D IWA and 100% throughput under the following assumptions:

- No wavefront error
- On-axis point source
- Ideal focal plane mask
- Fourier Optics (no propagation of edge diffraction through finitely sized optical elements)



Our SCDA effort goes from ideal concept to realistic implementation by taking into account these 3 effects

Focal plane mask



*Ideal PIAACMC calls for a phase-shifting disk with a fixed I/D radius
There is no demonstrable way to make such a mask in broadband light
→ we approximate it by a multi-zone physical device (mirror), which can be manufactured*

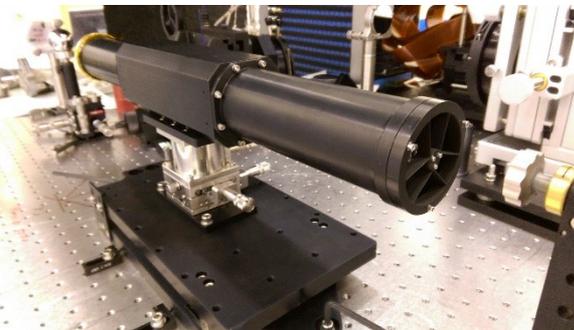
Multiple zones (sectors or hexagons) phase-shift light

Multiple zones interfere destructively inside the pupil across the science spectral bandwidth

No light is absorbed → ALL starlight sent to the LOWFS for efficient sensing of low-order aberrations

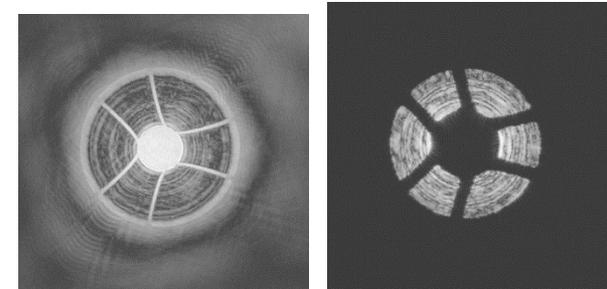
***Much of our SCDA activity has been to design manufacturable FPMs for PIAACMC
FPM co-optimized for broadband performance, stellar angular size (+ optional
resilience to known aberrations)***

PIAACMC SCDA design uses same approach as WFIRST PIAACMC (some hardware, technology heritage)



On-axis PIAACMC system (Gregorian telescope)

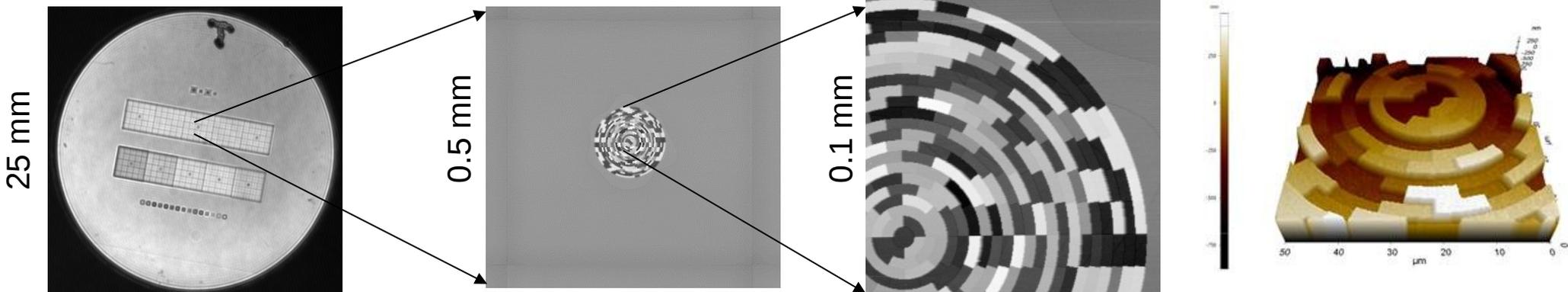
Single Lyot Stop → easy feed to LOWFS



Zygo phase

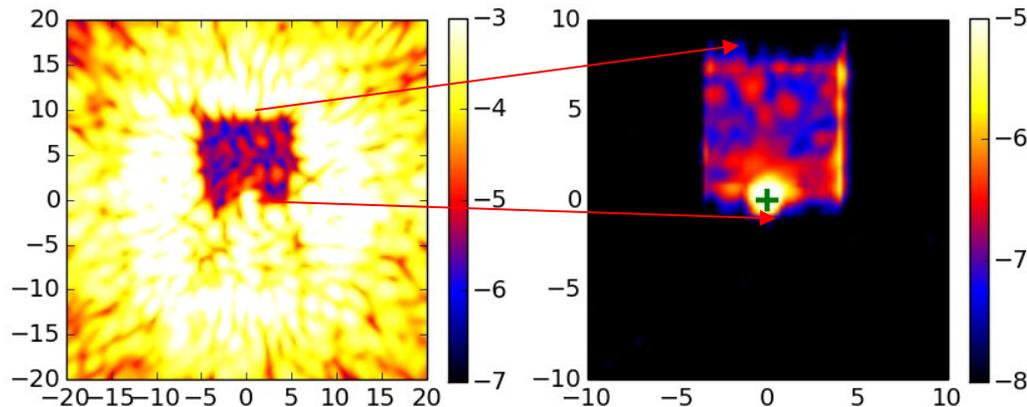
ZeMapper

AFM

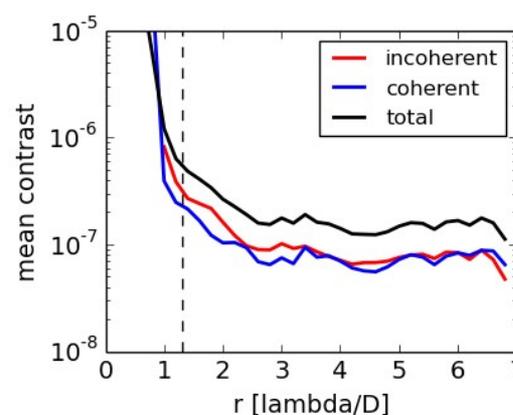


1 DM, 1-sided, $\pm 6 \lambda D$ before inserting field stop

field stop in



Reflective multi-zone focal plane mask



PIAACMC science trade space

Key advantages

- **High throughput, “undisturbed” PSF**
- **Access to small IWA (~1.0-1.5 I/D) ...** but comes with high sensitivity to stellar angular size
- **Maintains high performance on segmented aperture**

→ Brings additional potential science capabilities not accessible to “classical” coronagraph approaches working at larger IWA:

- **Longer wavelength science (near-IR):** star is smaller, planet is closer in (in I/D units), planet may have thermal emission (kicks in @ ~3+ μm)
- **Provides access to later-type stars.** Proxima Cen b -like targets: moderate contrast ($\sim 1\text{e-}7$) but small angular separation
- **Provides access to distant targets.** Small angular separation, small stellar size

→ PIAACMC/SCDA effort key goals:

- (1) Demonstrate viable architecture for segmented aperture: managing edge diffraction with realistic optical design and manufacturable components
- (2) Demonstrate/quantify additional science capabilities enabled by small IWA access
- (3) Can PIAACMC @ segmented aperture ALSO operate in the more conventional performance regime (contrast $\sim 1\text{e-}9$ / $1\text{e-}10$ at 4 I/D) ?

Key findings

(1) Demonstrate viable architecture for segmented aperture → Completed to 1e-8 level, now pushing deeper

We have produced designs that deliver PIAACMC key IWA & throughput advantages: ~1 I/D IWA, 70% throughput in broadband light

Designs are matched to realistic optical design and components manufacturing capabilities, as demonstrated on HCIT with PIAACMC testbed

(2) Demonstrate/quantify additional science capabilities → Ongoing, promising... but needs further improvement (stellar angular size)

Performance limited by stellar angular size

With stellar size = 2% I/D, raw contrast ~1e-7. Smaller stellar size → deeper contrast

→ does bring in unique near-IR science, planets around M-type stars

... but needs further improvement

(3) Can PIAACMC @ segmented aperture ALSO (simultaneously) operate in the more conventional performance regime (contrast ~1e-9 / 1e-10 at 4 I/D) ? → Optimization of high perf solution at 4 I/D not been seriously started yet. Likely requires changes in architecture/hybrid (some progress with APLC / PIAACMC hybrid).

Stellar angular size is a significant issue even at >3 I/D → we have not yet demonstrated deep contrast with small-IWA PIAACMC

Does an architecture offering simultaneously access to small IWA and deep contrast at > 3I/D exist ?

Promising avenues currently under investigation, but with reduced throughput:

APLCMC architecture does offer improved sensitivity to stellar angular size

APLC + PIAACMC : apodize pupil to deliver deep contrast @ > 3 I/D, use PIAACMC for < 3 I/D

PIAACMC design process

Design is a 2-step process

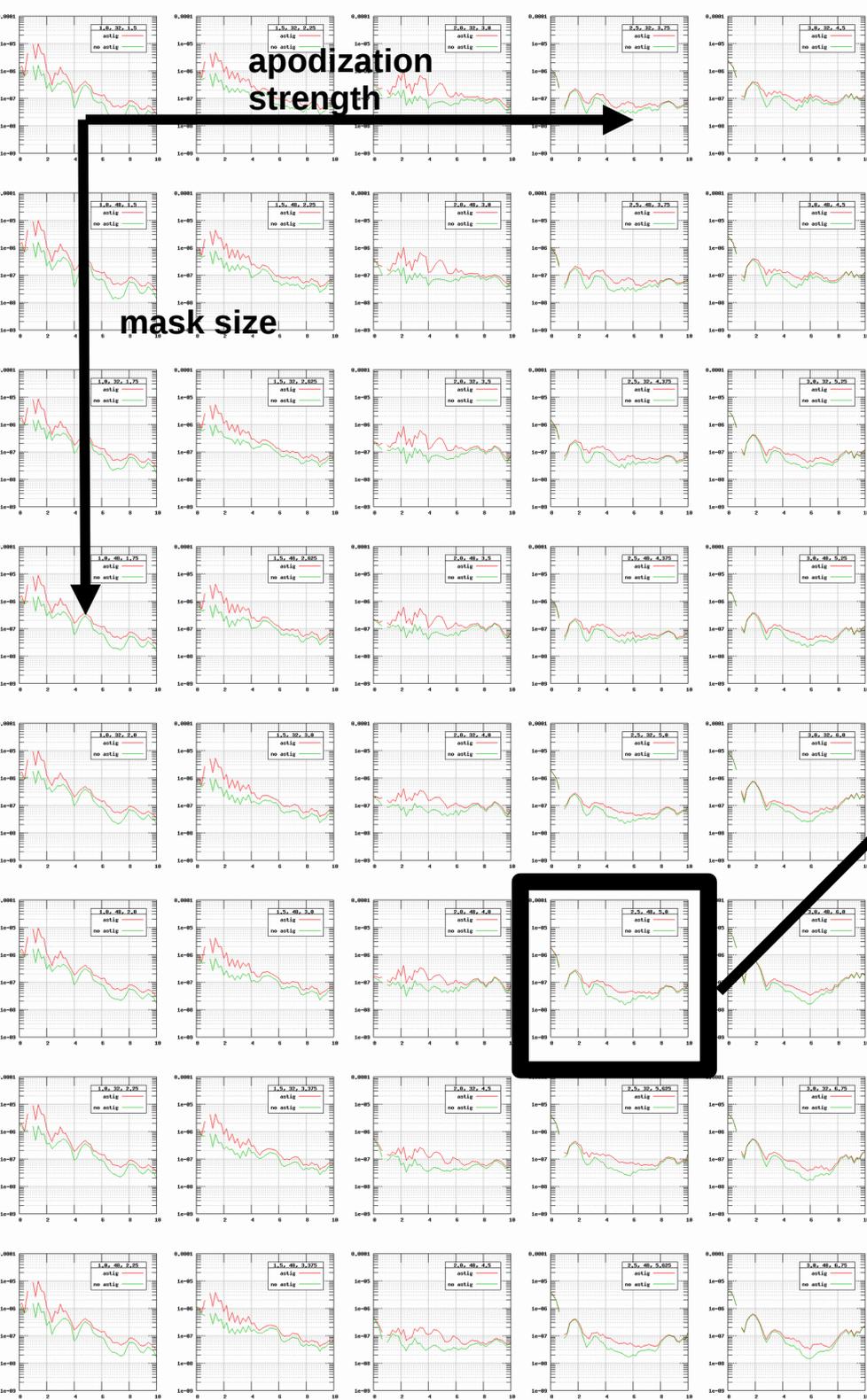
- (1) Design PIAACMC (or APLCMC) in monochromatic light, point source, and ideal focal plane mask
- (2) Add chromaticity, stellar angular size and physical mask → optimize mask zone thicknesses

PIAACMC design software

Source code: www.github.com/oguyon/PIAACMCdesign

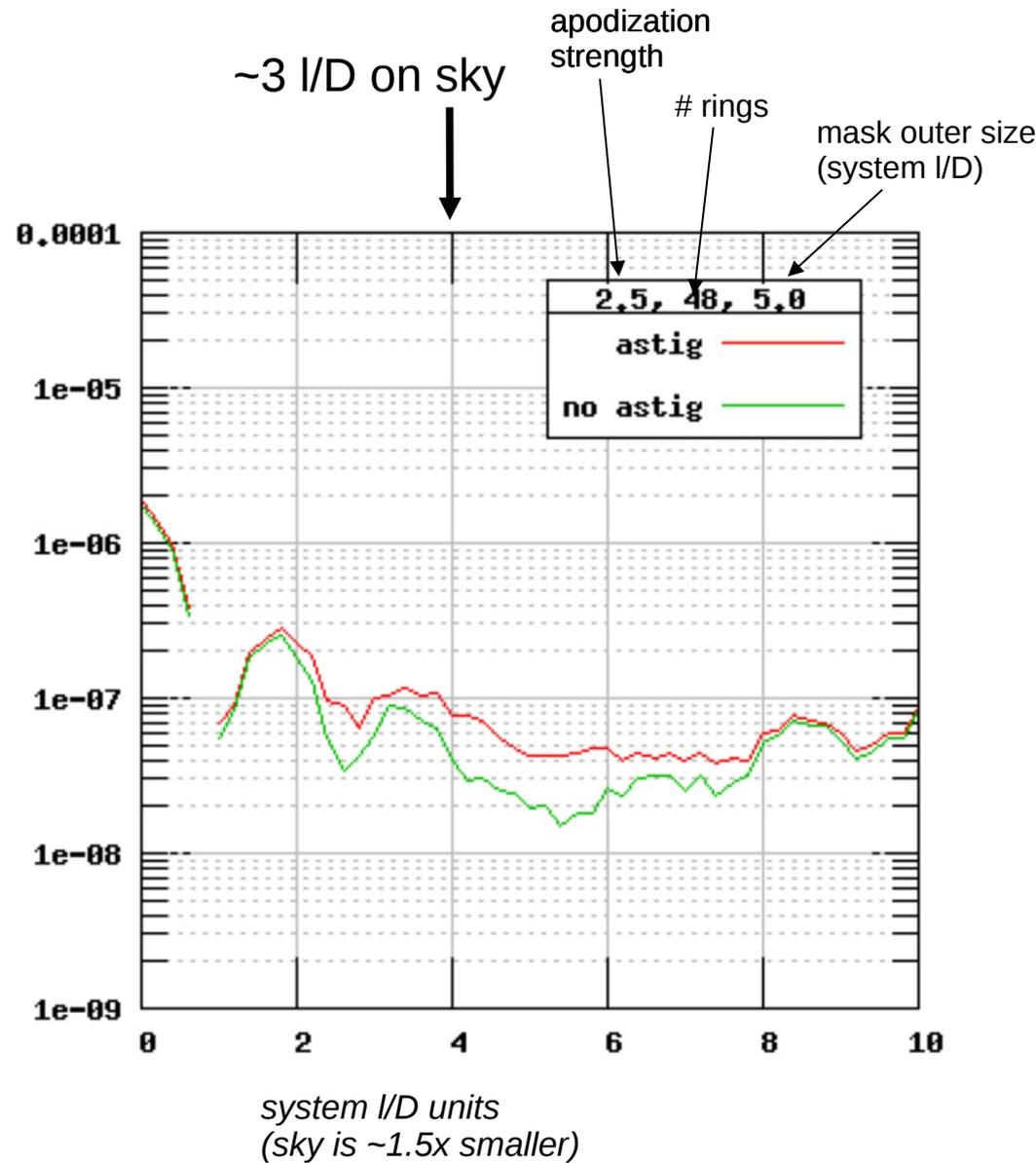
- C code, runs on Linux & OS-X systems, uses GPU acceleration
- Development & single/few design(s) evaluation on computers at UofA, Hawaii & Ames
- Preparing for use of NASA Ames hyperwall cluster for rapid parameter exploration (128-node cluster, each: 20 cores + GPU, 64GB mem, 646 Tflop/s)
- Independent verification process of results @ Ames under development

Extensive parameter scan @ Ames hyperwall (example shown here for WFIRST/polarization study)



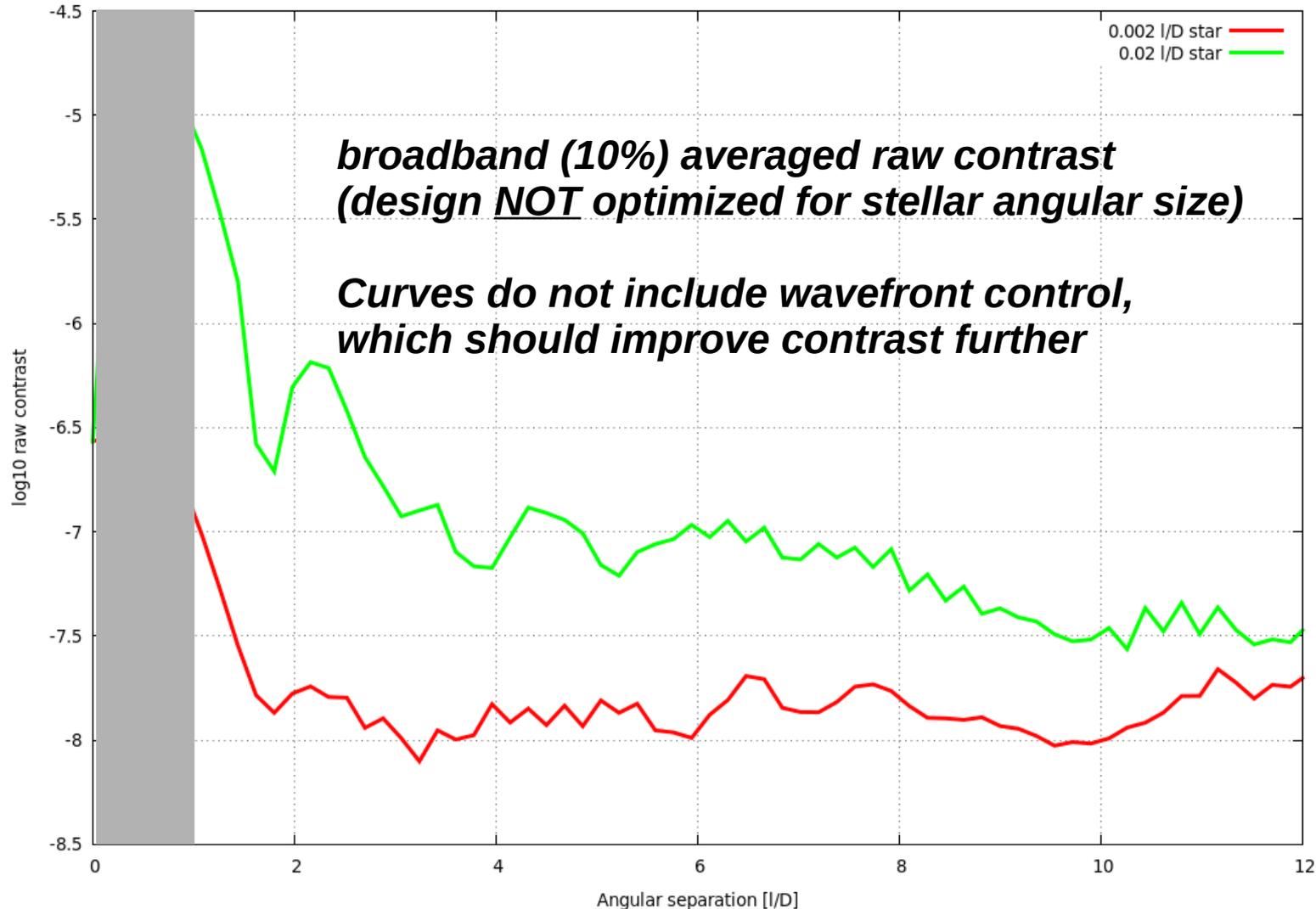
apodization
strength

mask size



Design #1: “Aggressive” PIAACMC, 3-ring SCDA aperture

High perf. near IWA for point source, but very sensitive to stellar angular size



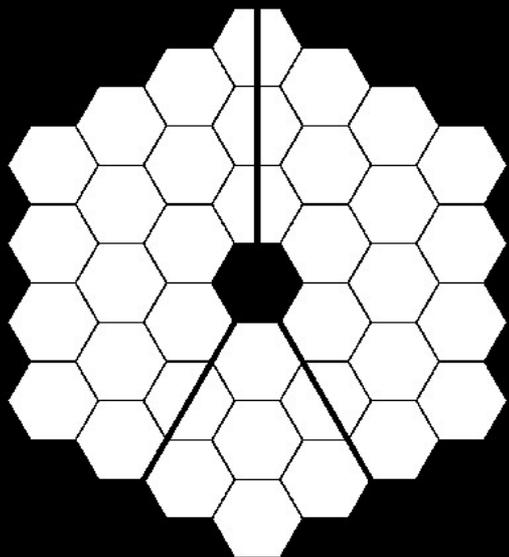
- 1.0 I/D IWA
- 70% throughput
- Single Lyot stop (Performance improves with >1 Lyot stop)
- No invPIAA (simpler)

Optimized for:

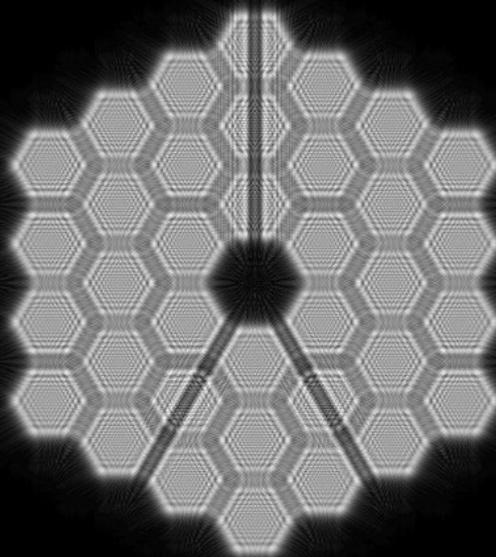
- 10% band centered at 565nm
- point source
- Optics diam = 2x beam size

Focal plane mask:

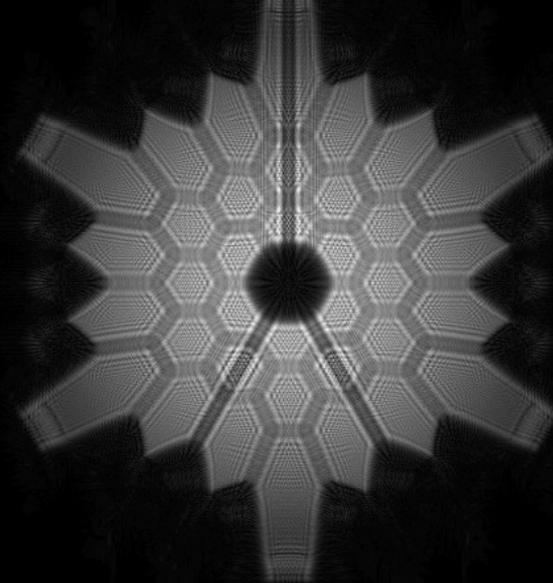
- 0.9 I/D nominal size
- 32 rings, 3.6 I/D outer zone



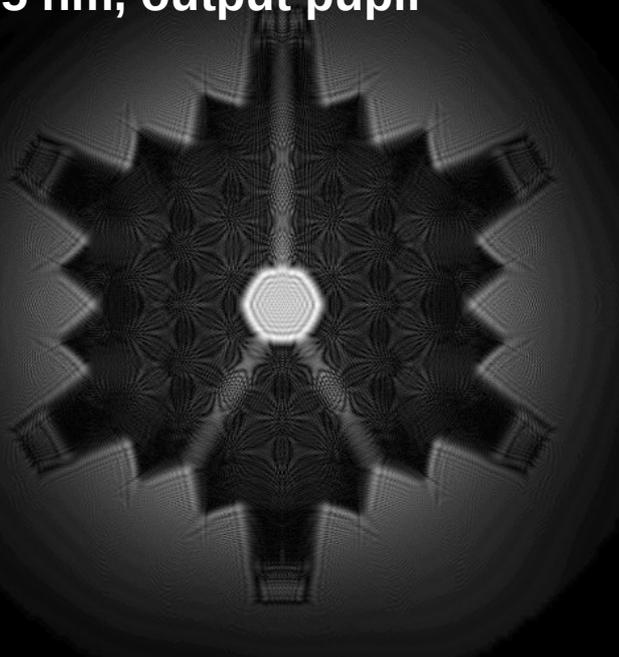
565 nm



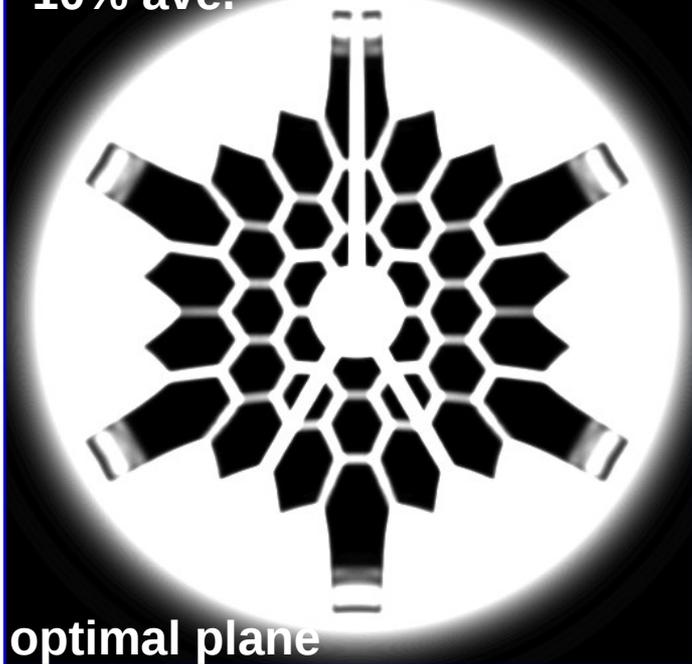
565 nm



565 nm, output pupil

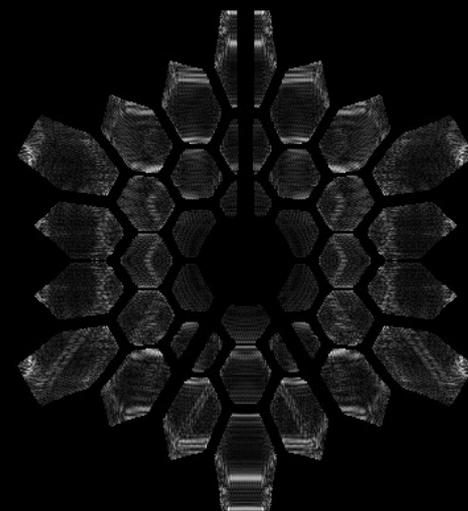


10% ave.



optimal plane

565 nm



0.0036

0.0072

0.0109

0.0145

0.0182

0.0218

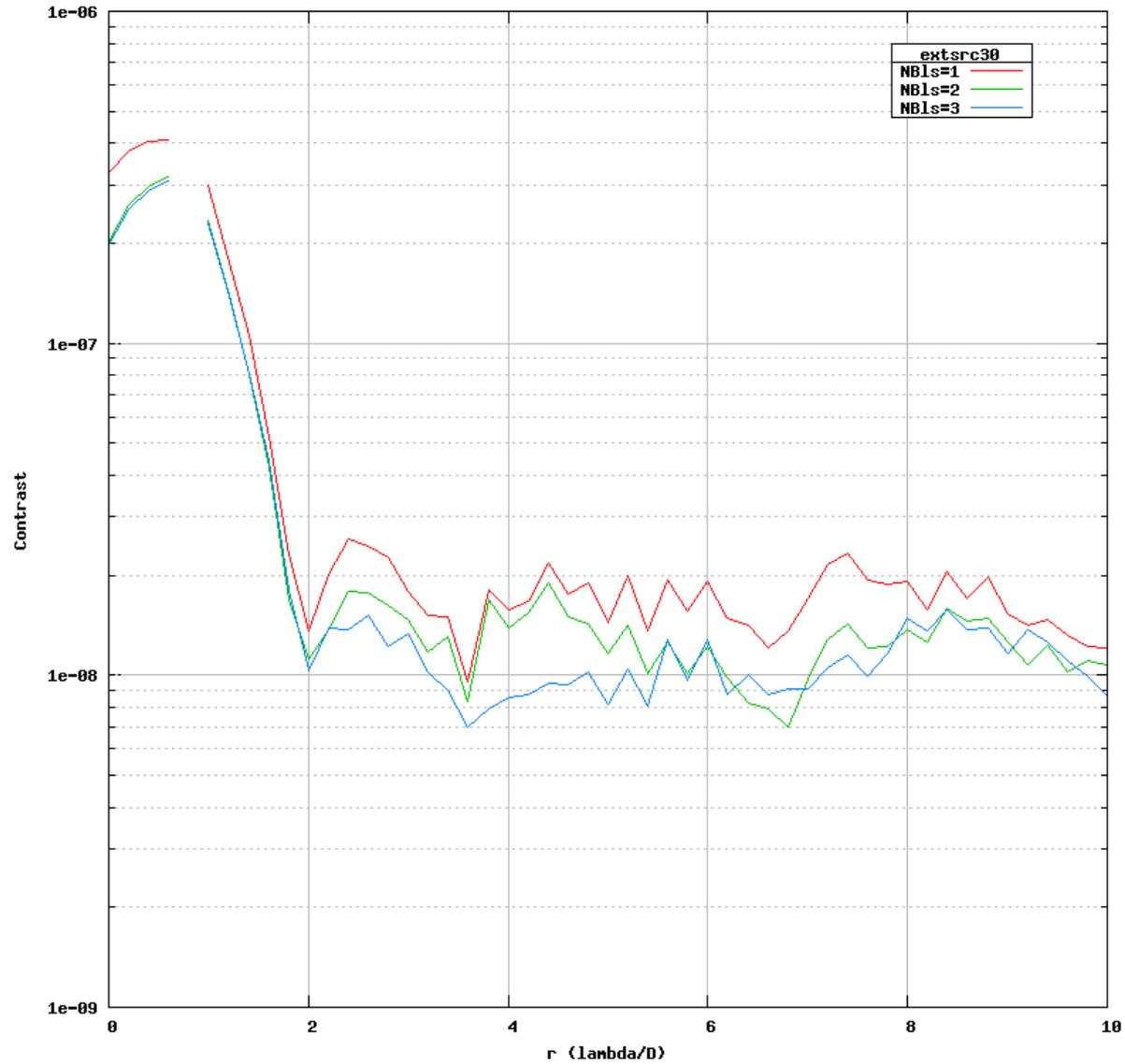
0.0254

0.0291

0.0327

Brightness scale is different between images

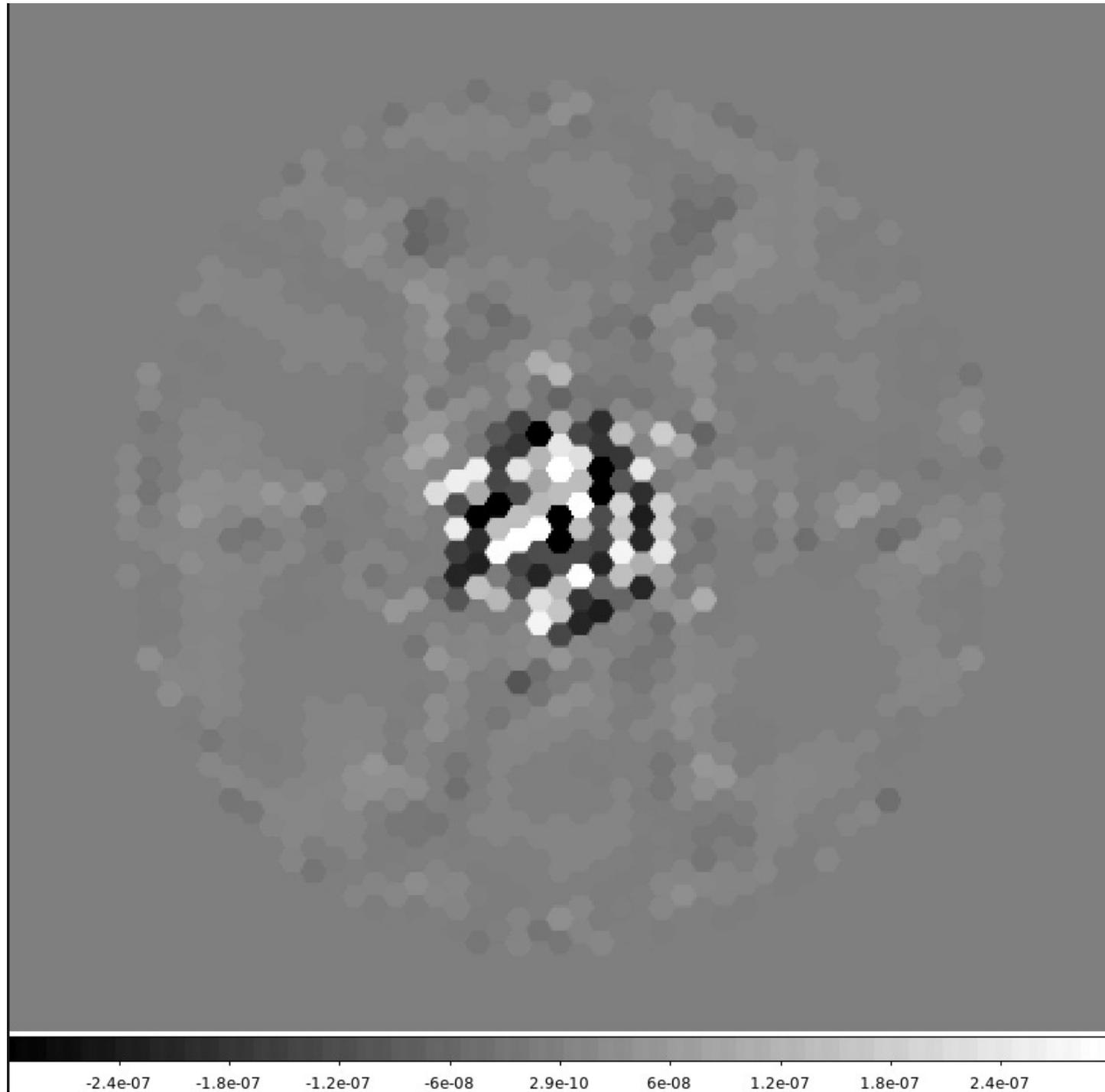
Multiple Lyot Stops help



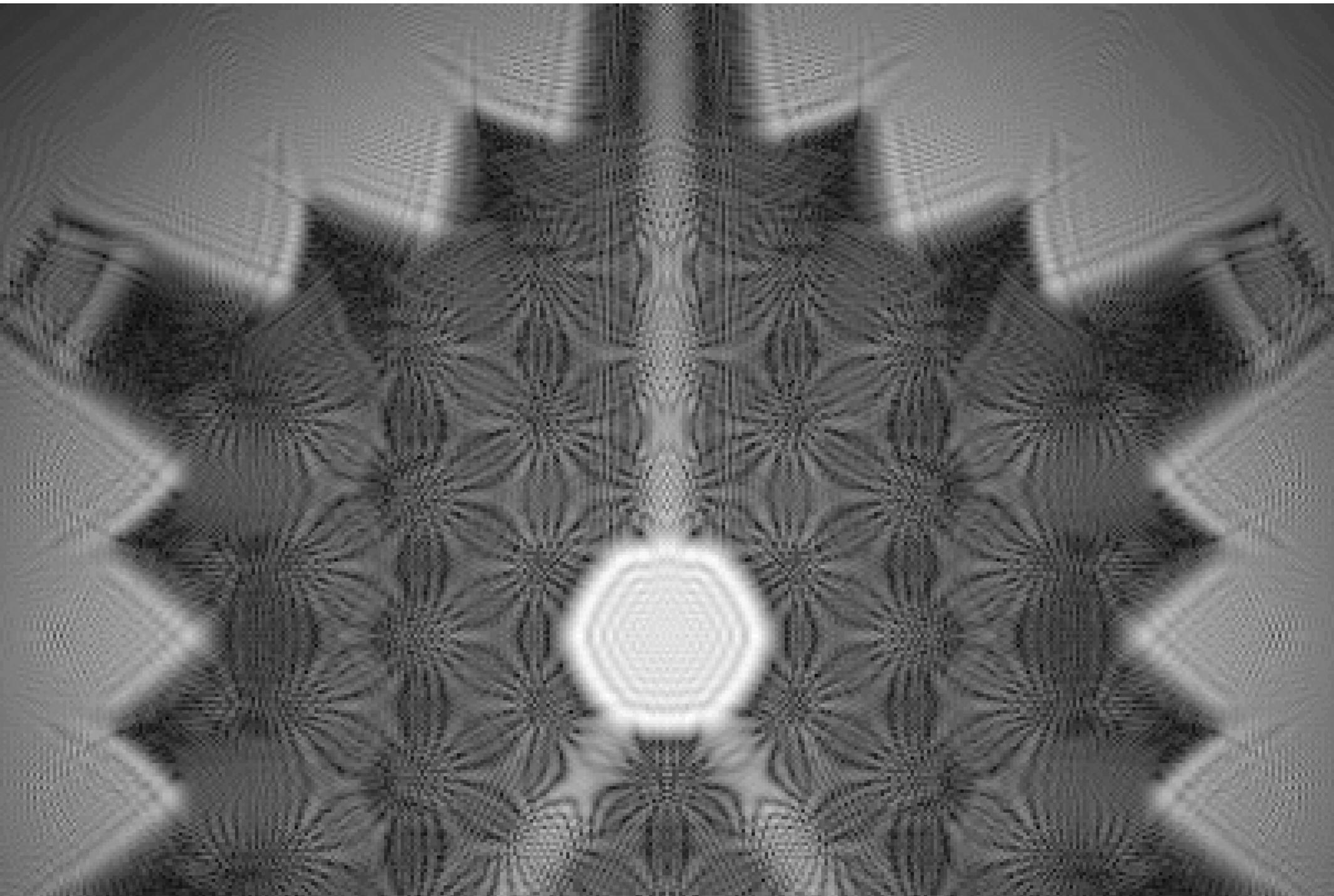
Focal plane mask design (mirror)

Sag +/- 600nm

Little sag outside 1 I/D



540 nm – diffraction effects due to segments, beam truncation, PIAA



0.021

0.084

0.19

0.34

0.53

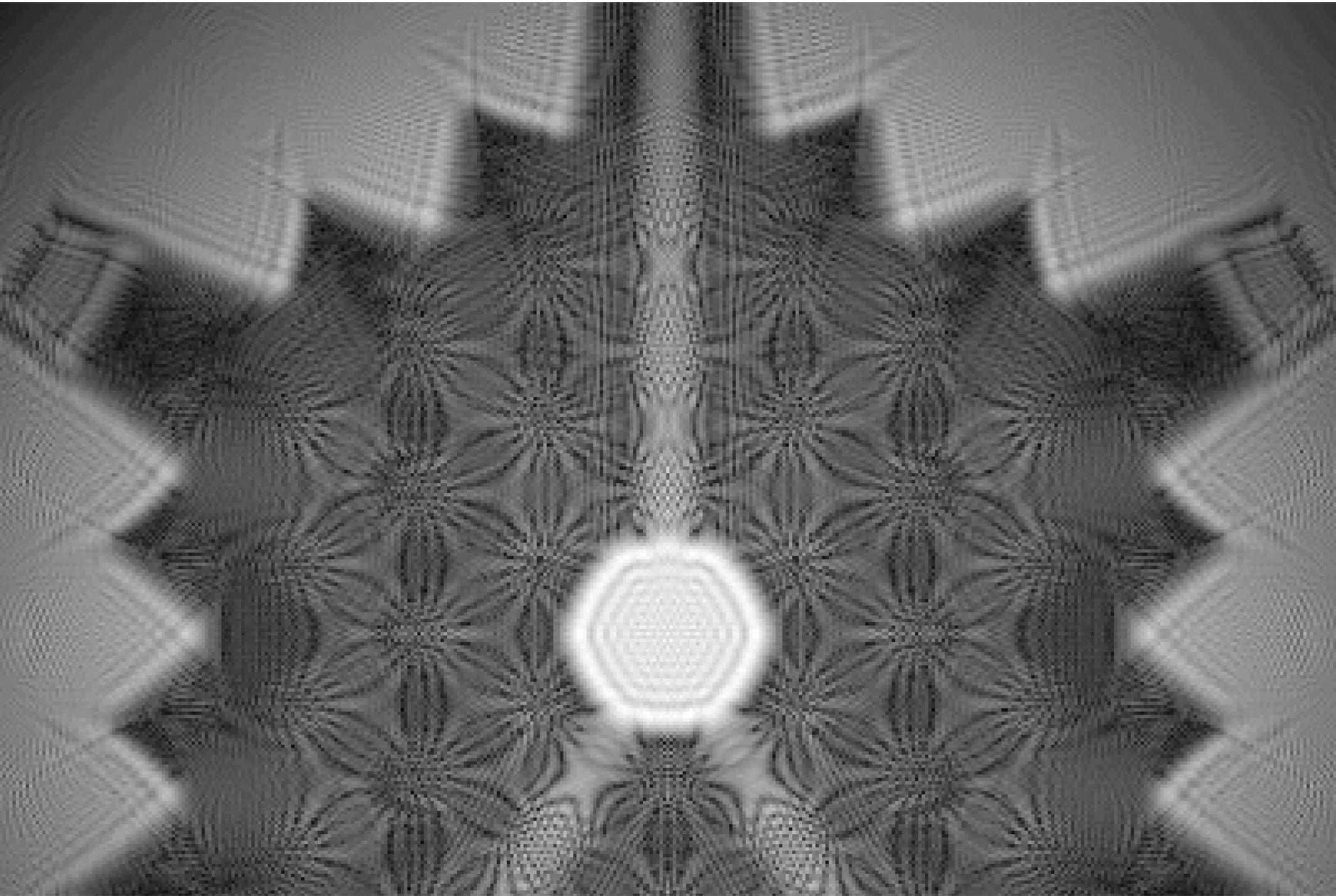
0.76

1

1.3

1.7

590 nm – diffraction effects due to segments, beam truncation, PIAA



0.02

0.081

0.18

0.33

0.51

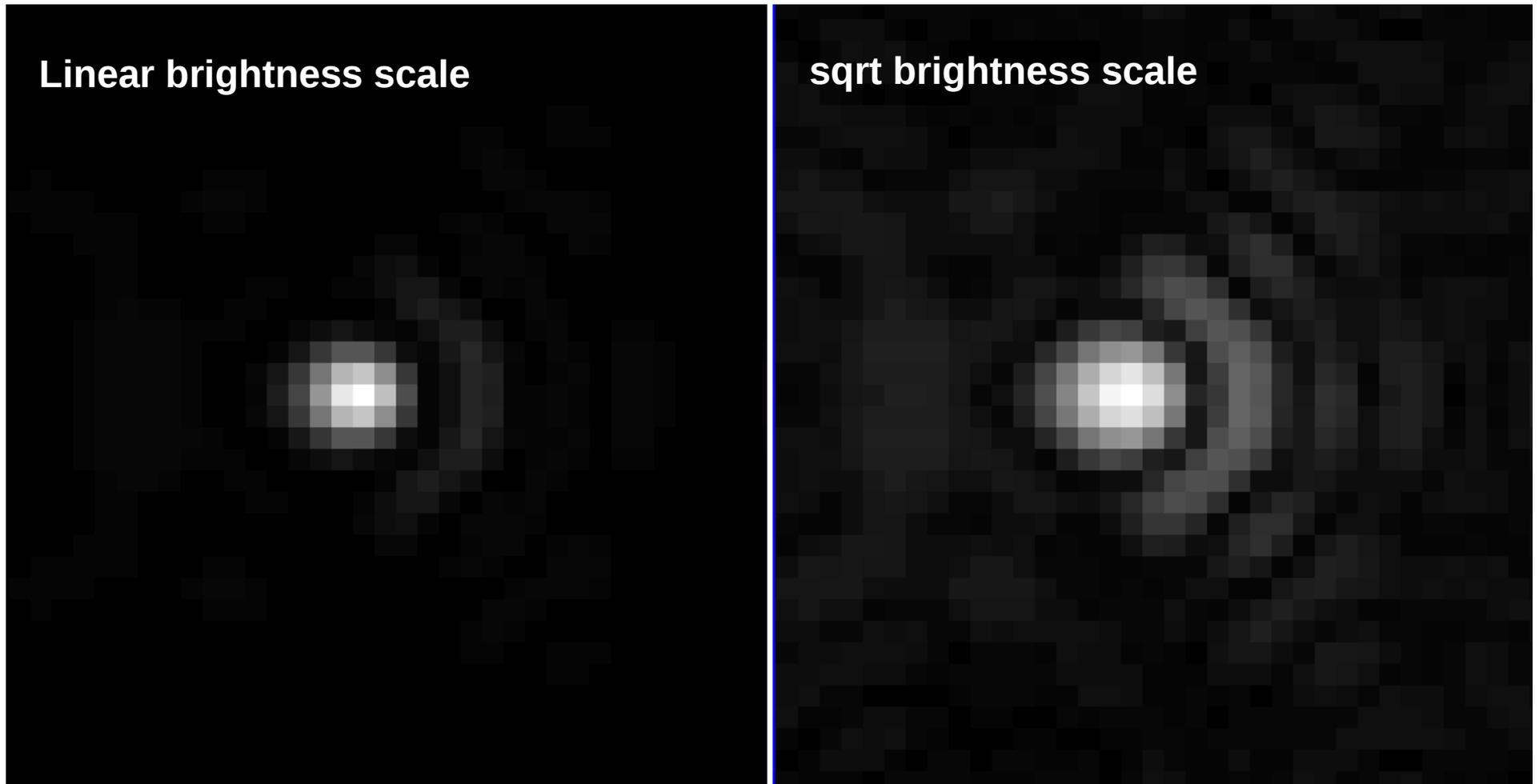
0.74

1

1.3

1.7

Off-axis image quality @ 5 I/D (contrast reference)

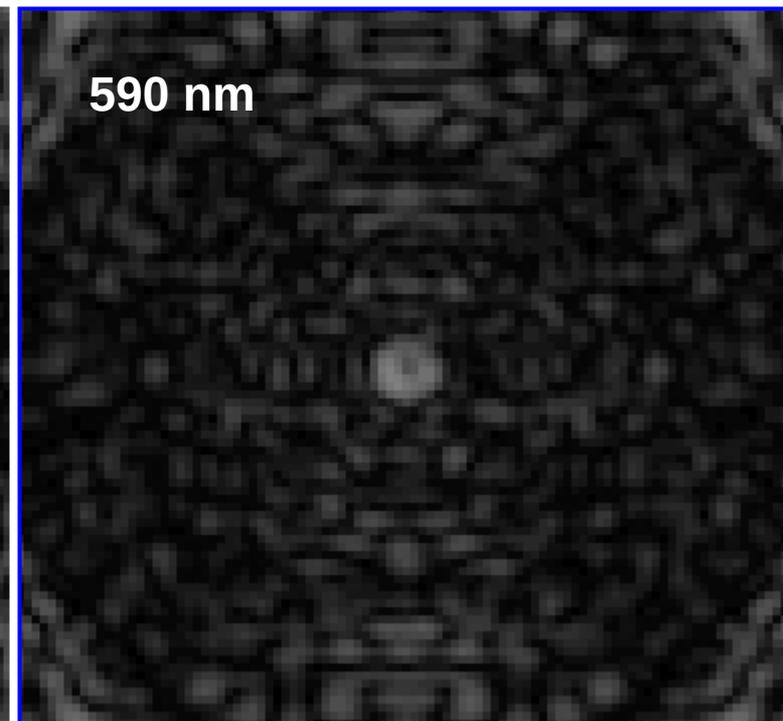
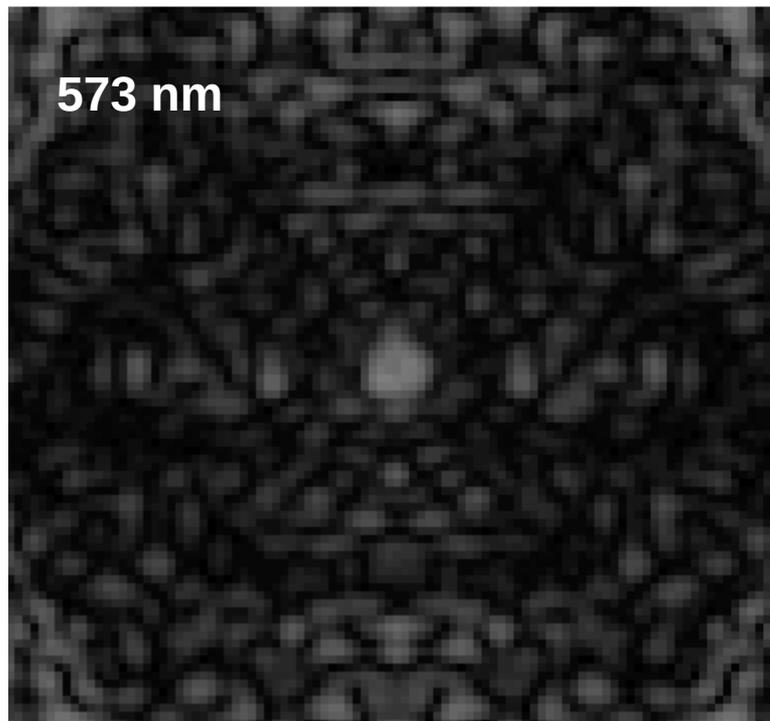
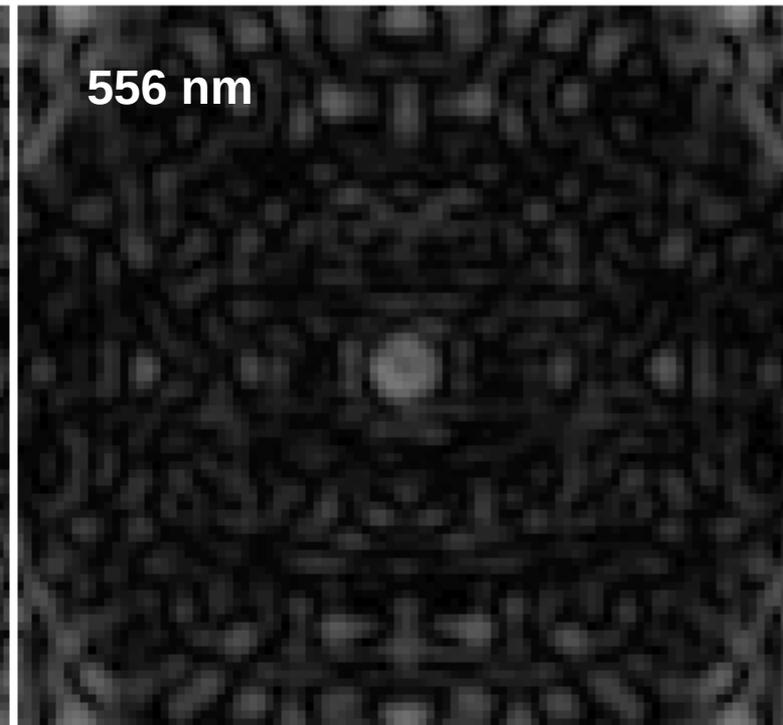
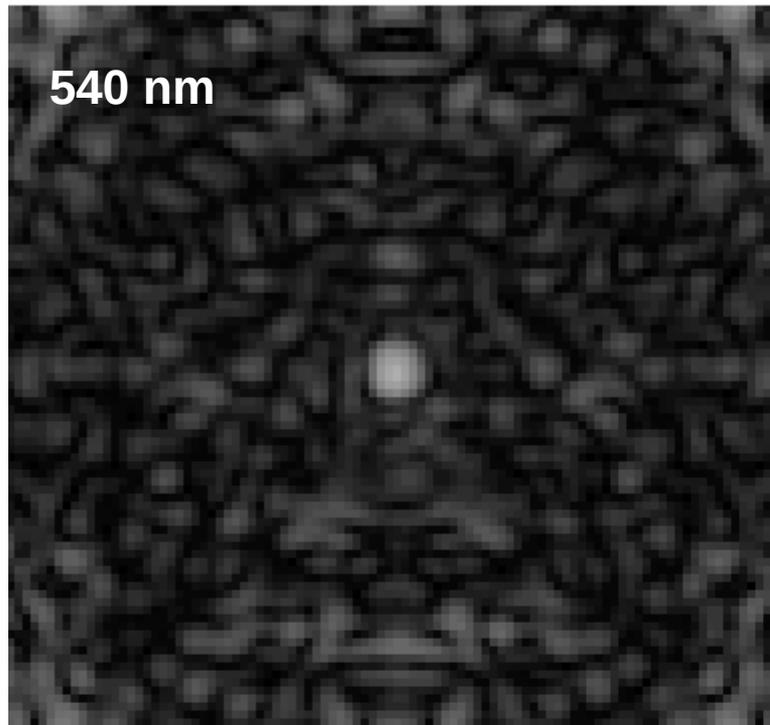


Off-axis PSF has similar core throughput to full aperture nominal PSF
Fainter Airy ring (thanks to apodization), but some off-axis coma

High contrast PSF is strongly chromatic

- Effect of numerical sampling to be evaluated
- Wavefront control is unlikely to have significant leverage on chromatic residual

→ need to adopt finer sampling (more computing time)



Design #2: APLCMC, 3-ring SCDA aperture

Lower throughput, improved sensitivity to stellar angular size

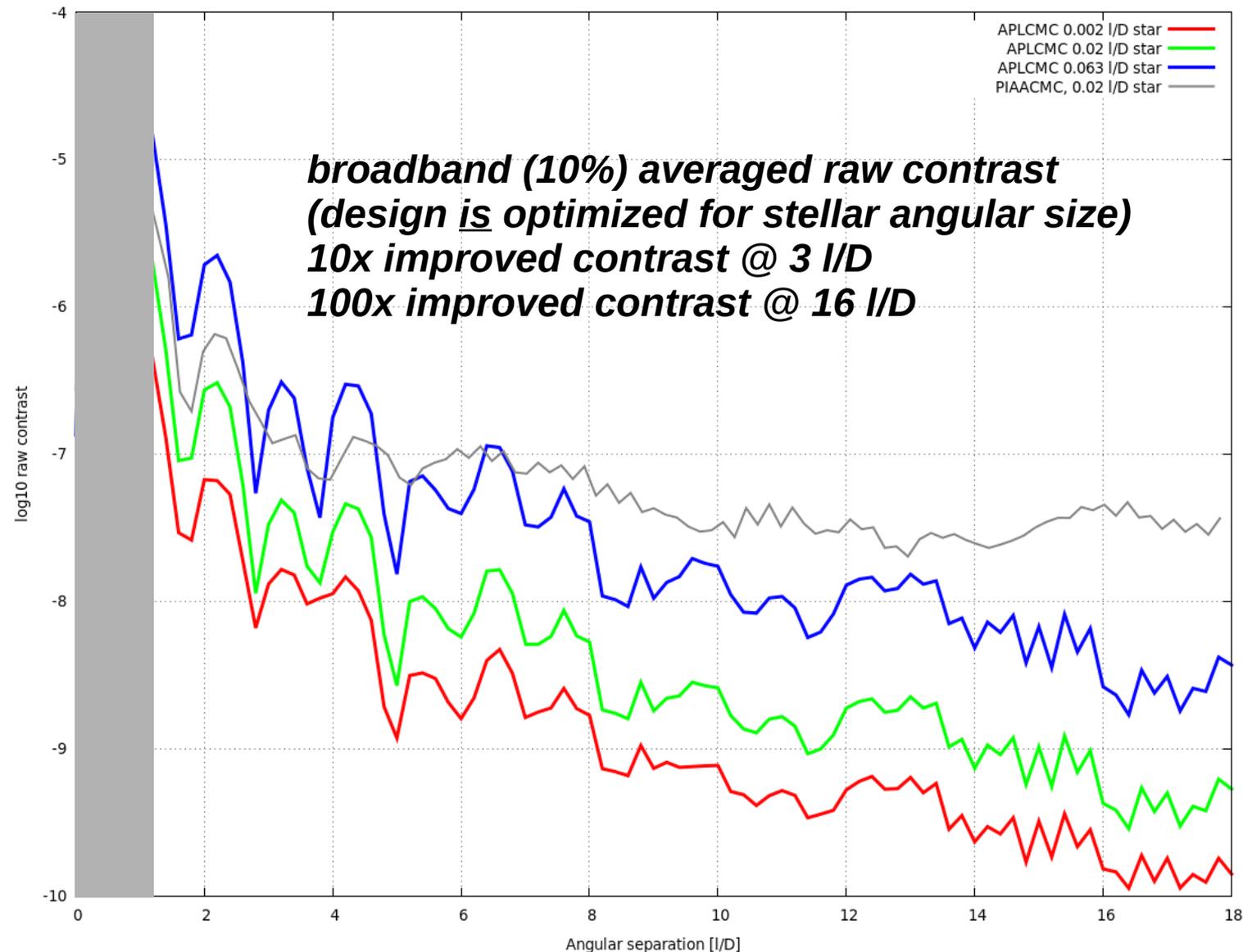
- ~1.1 I/D IWA
- 46% throughput
(**pupil apodizer**)
- Single Lyot stop

Optimized for:

- 10% band centered at 565nm
- **0.02 I/D source**
- Optics diam = 2x beam size

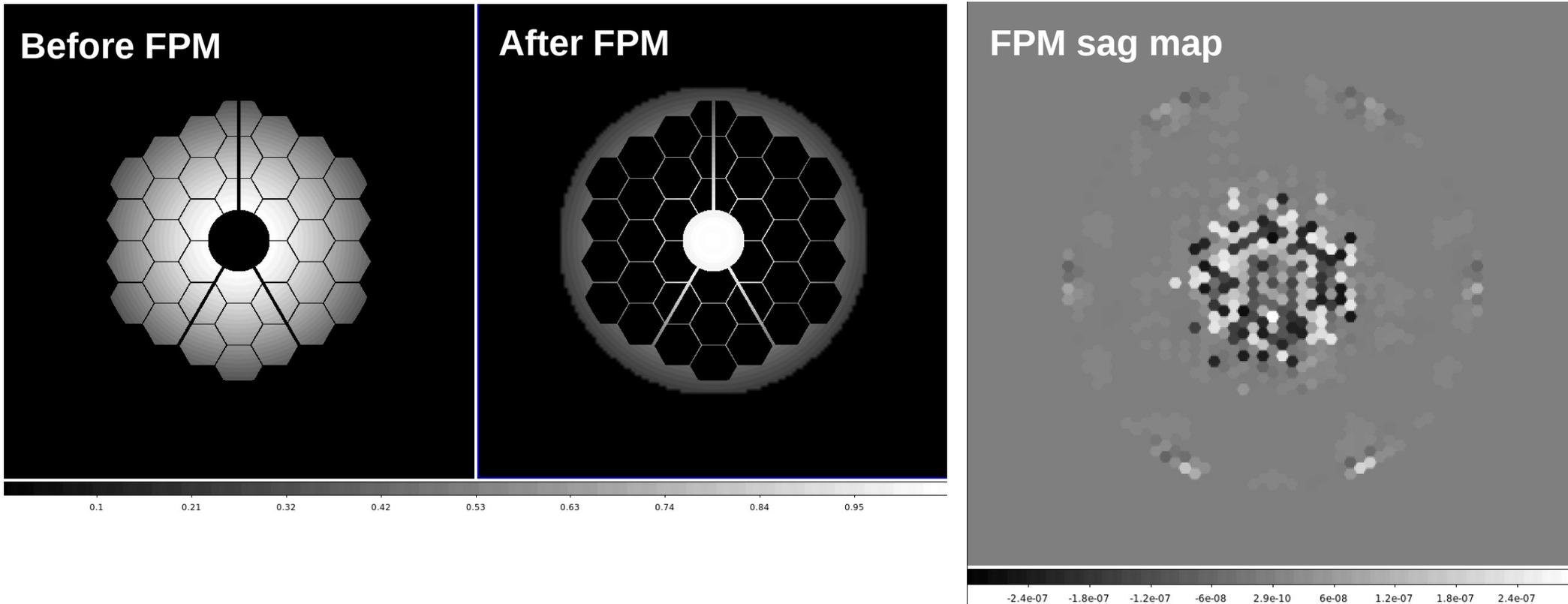
Focal plane mask:

- **1.0 I/D** nominal size
- 32 rings, **4.0 I/D** outer zone



Design #2: APLCMC, 3-ring SCDA aperture

Lower throughput, improved sensitivity to stellar angular size



Warnings:

- This design was not simulated using truncated optics in intermediate planes (uses Fourier transforms, not actual physical propagations)
 - Does not fully capture segment edge diffraction effects in realistic optical design
- Ideal apodizer assumed (how to manufacture it ? Binary mask ?)

Preparing for lab demo: Exploring FPM manufacturing options @ UofA

UA Link Award → A small graduate-led (J. Knight) team will generate pilot data for coronagraph mask manufacturing efforts during the 2016-2017 academic year

Major Tasks:

Manufacture coronagraph focal plane masks

Focus on in-house capabilities: binary etching e-beam lithography into Si with a mask-aligner (MA6)

Testability: Subaru telescope, etching into Si wafer; master silicone mold-to-UV epoxy → AR coatings are important for multi-wavelength performance!

Draw from previous/current device manufacturing efforts, e.g. JPL MDL Gen 3 PIAACMC, SNF achromatic PIAACMC FPMs (K. Newman), Subaru masks at Cornell

Survey local and national manufacturing capabilities

Create a database of nanofabrication facility processes/tools geared toward FPM creation

Establish collaborative relationships with coronagraph research groups around the world – here's what *we* do, what do *you* do? How can we help?

There are multiple ways to make masks already, yet the space of manufacturing is relatively unexplored such that a “best” process has been developed, esp. for PIAACMC masks. While there is a path forward from design to manufacturing of these devices, we have the flexibility to take different approaches presently.

Conclusions & Next Steps

Demonstrated PIAACMC design on segmented aperture in realistic optical system, 10% band
Achieves ~1.0 I/D IWA, 70% throughput

Contrast floor at $1e-8$ may be due to sampling effects (under investigation)

Contrast limited by stellar angular size

→ **PIAACMC can deliver low IWA + high throughput, but sensitivity to stellar angular size increases as IWA decreases**

Implementation is compatible with realistic optical design and manufacturing capabilities

PIAACMC unlikely to have strong aperture geometry preference (will confirm by running designs on all apertures)

Demonstrated that hybridization with APLC and focal plane mask optimization can mitigate sensitivity to stellar angular size

→ **Encouraging step toward coronagraph solution offering simultaneously small IWA and maintains deep contrast at larger separations**

Next steps:

- Simulate less aggressive PIAACMC (larger IWA)
- Investigate sampling effects
- Include wavefront control
- Explore Hybrids
- Code improvements, validation and verifications → run batch scans on Ames HyperWall
- Compare results with fundamental limits